

### Amendments to the Claims

The listing of claims replaces the previous version, and the listing of claims:

### Listing of Claims

1-5. (cancelled)

6. (currently amended) A plasma-enhanced processing apparatus ~~as claimed in claim 5, comprising:~~

a process chamber for processing a substrate therein having a wall,

a pumping system communicating with said process chamber for exhausting gas in the process chamber,

a gas-introduction system that introduces process gas into said process chamber,

plasma-generation means that generates plasma in said process chamber by applying energy to said process gas,

a substrate holder that holds said substrate in said process chamber,

an opposite electrode disposed in the process chamber to face said substrate held by said substrate holder, and including a front board facing the substrate holder, a clamping plate disposed at a front side of the front board close to the substrate holder so that an area of the front board not covered by the clamping plate is exposed to plasma, and a main body installed on the wall of the process chamber and disposed at a back side of the front board opposite to the front side so that said front board is clamped between the clamping plate and the main body,

said clamping plate being fixed so that said clamping plate presses said front board toward said main body and a back surface

of the front board is contacted and pressed uniformly onto the main body,

said front board being fixed to said main body by pressure of said clamping plate toward said main body with no screw penetrating said front board, and

a protector covering a front surface of said clamping plate so that said front surface of the clamping plate is not exposed to said plasma,

wherein said front board has a stepped portion at a periphery sandwiched by the main body and the clamping plate, the protector is located on the stepped portion and a front surface of the protector is on the same plane as the front surface of said front board, and

no projection is formed on the front surfaces of the front board and the protector both exposed to the plasma.

7. (previously presented) A plasma-enhanced processing apparatus as claimed in claim 6, wherein said front board is made of silicon poly-crystal or silicon mono-crystal.

8-19. (cancelled)

20-21. (cancelled)

22. (currently amended) A plasma-enhanced processing apparatus as claimed in claim 21 comprising:

a process chamber for processing a substrate therein having a wall,

a pumping system communicating with said process chamber for exhausting gas in the process chamber,

a gas-introduction system that introduces process gas into said process chamber,

plasma-generation means that generates plasma in said process chamber by applying energy to said process gas,

a substrate holder that holds said substrate in said process chamber,

an opposite electrode disposed in the process chamber to face said substrate held by said substrate holder, and including a front board facing the substrate holder, a clamping plate disposed at a front side of the front board close to the substrate holder so that an area of the front board not covered by the clamping plate is exposed to plasma, and a main body installed on the wall of the process chamber and disposed at a back side of the front board opposite to the front side so that said front board is clamped between the clamping plate and the main body,

said clamping plate being fixed so that said clamping plate presses said front board toward said main body and a back surface of the front board is pressed uniformly onto the main body,

said front board being fixed to said main body by pressure of said clamping plate toward said main body with no screw penetrating said front board,

a protector covering a front surface of said clamping plate so that said front surface of the clamping plate is not exposed to said plasma, and

screws fixing the clamping plate to the opposite electrode, wherein the protector covers heads of the screws so that the heads of the screws are not exposed to said plasma, and the screws do not contact the front board,

wherein the front board has a stepped portion at a periphery thereof that is sandwiched by the main body and the clamping plate, the protector is located in a space formed by the stepped portion of the front board, and a front surface of the protector is on a same plane as the front surface of the front board, and

no projection is formed on the front surfaces of the front board and the protector both exposed to the plasma.

23-26. (cancelled)

27. (new) A plasma-enhanced processing apparatus as claimed in claim 22, wherein said front board is made of silicon poly-crystal or silicon mono-crystal.

28. (new) A plasma-enhanced processing apparatus as claimed in claim 6, wherein said protector is made of quartz or carbon.

29. (new) A plasma-enhanced processing apparatus as claimed in claim 22, wherein said protector is made of quartz or carbon.